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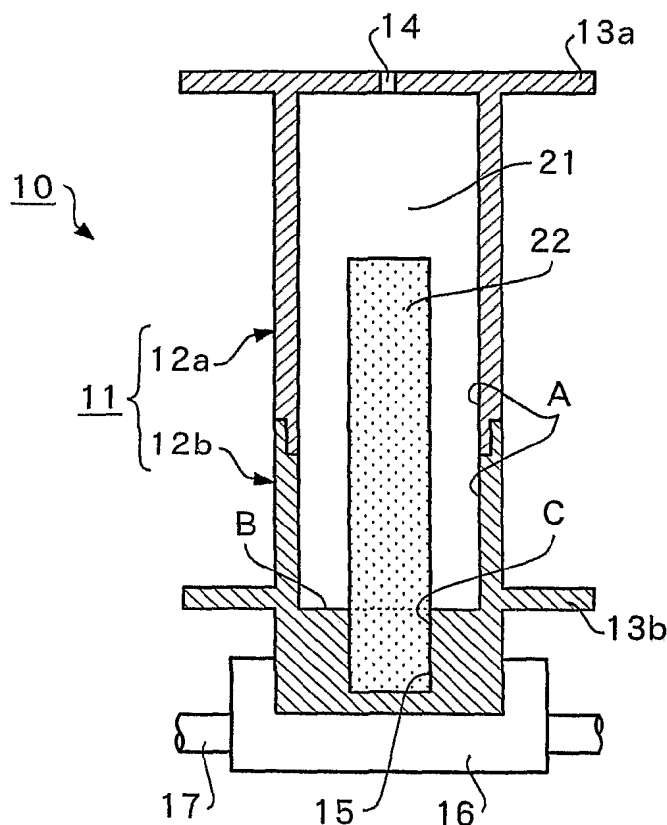
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(54) Title: VACUUM DEPOSITION METHOD AND SEALED-TYPE EVAPORATION SOURCE APPARATUS FOR VACUUM
DEPOSITION



(57) Abstract: A vacuum deposition method is provided. In the vacuum deposition for evaporating a sublimation evaporation material (22), the gas sealed-type heating container (11) has the blast aperture (14) and an area for evaporating the evaporation material by the radiation heat from the inner surface thereof. The holder (15) holds an evaporation material in a region in which the evaporation material does not evaluate due to the heatconduction from the heating container (11). Thus, the generated vapor is emitted from the blast aperture (14) into the deposition subject surface outside the container.



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